

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	14	US-3019799-\$.DID. OR US-4855023-\$.DID. OR US-5039349-\$.DID. OR US-5063949-\$.DID. OR US-5301701-\$.DID. OR US-5806543-\$.DID. OR US-5836321-\$.DID. OR US-5882404-\$.DID. OR US-5937878-\$.DID. OR US-6016818-\$.DID. OR US-6253775-\$.DID. OR US-6273108-\$.DID. OR US-6279587-\$.DID. OR US-6379538-\$.DID.	US-PGPUB; USPAT	OR	ON	2006/01/11 16:06
S2	1403	(wafer or semiconductor or substrate or workpiece) near10 (roll\$3) same nozzle	US-PGPUB; USPAT	OR	ON	2006/01/12 10:25
S3	130	"134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (roll\$3) same nozzle	US-PGPUB; USPAT	OR	ON	2006/01/11 16:15
S4	67	"134"/902,172.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (roll\$3) same nozzle	US-PGPUB; USPAT	OR	ON	2006/01/11 16:17
S5	192	"134"/902,172.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (roll\$3)	US-PGPUB; USPAT	OR	ON	2006/01/11 16:17
S6	140	"134"/902,172.ccls. and (wafer or semiconductor or substrate or workpiece) near10 vertical near10 (roll\$3 or rotat\$4)	US-PGPUB; USPAT	OR	ON	2006/01/11 16:20
S7	212	"134"/902,172.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (roll\$3 or wheel)	US-PGPUB; USPAT	OR	ON	2006/01/11 16:20
S8	20	S7 not S5	US-PGPUB; USPAT	OR	ON	2006/01/11 16:20
S9	557	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 (roll\$3) same nozzle	US-PGPUB; USPAT	OR	ON	2006/01/12 10:27

S10	10398	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 (roll\$3)	US-PGPUB; USPAT	OR	ON	2006/01/12 10:27
S11	5585	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 (roller)	US-PGPUB; USPAT	OR	ON	2006/01/12 10:28
S12	1882	S11 and (wafer or semiconductor or substrate or workpiece).ti.	US-PGPUB; USPAT	OR	ON	2006/01/12 10:28
S13	95	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) near5 vertical and (wafer or semiconductor or substrate or workpiece) near10 (roller)	US-PGPUB; USPAT	OR	ON	2006/01/12 10:28
S14	171	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) near5 vertical\$3 and (wafer or semiconductor or substrate or workpiece) near10 (roller)	US-PGPUB; USPAT	OR	ON	2006/01/12 11:01
S15	1238	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 rotat\$3 near5 (roller)	US-PGPUB; USPAT	OR	ON	2006/01/12 11:29
S16	567	S15 and (wafer or semiconductor or workpiece or substrate).ti.	US-PGPUB; USPAT	OR	ON	2006/01/12 11:02
S17	69	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 rotat\$3 near5 (roller) and (nozzle or fluid near5 inject\$3) near5 (adjust\$3 or angl\$3)	US-PGPUB; USPAT	OR	ON	2006/01/13 09:51
S18	69	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 rotat\$3 near5 (roller) and (nozzle or fluid near5 inject\$3) near5 (adjust\$3 or angl\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 13:59

S19	45	(wafer or semiconductor or substrate or workpiece) near10 (plurality or multiple or several) near10 (clean\$3 or wash\$3) and (wafer or semiconductor or substrate or workpiece) near10 rotat\$3 near5 (roller) and (nozzle or fluid near5 inject\$3) near5 (adjust\$3 or angl\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 14:00
S20	55	(wafer or semiconductor or substrate or workpiece) near10 (plurality or multiple or several) near10 (clean\$3 or wash\$3) and (wafer or semiconductor or substrate or workpiece) near10 rotat\$3 near5 (roller or wheel) and (nozzle or fluid near5 inject\$3) near5 (move or moving or movable or adjust\$3 or angl\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 14:21
S21	100	(wafer or semiconductor or substrate or workpiece) near10 (plurality or multiple or several) near10 (clean\$3 or wash\$3) and (wafer or semiconductor or substrate or workpiece) near10 (roller or wheel) and (nozzle or fluid near5 inject\$3) near5 (move or moving or movable or adjust\$3 or angl\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 14:21
S22	111	(wafer or semiconductor or substrate or workpiece) near10 (plurality or multiple or several) near10 (clean\$3 or wash\$3) and (wafer or semiconductor or substrate or workpiece) near10 (roller or wheel) and (nozzle or fluid near5 inject\$3) near10 (move or moving or movable or adjust\$3 or angl\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 14:23
S23	77	(wafer or semiconductor or substrate or workpiece) near10 (plurality or multiple or several) near10 (clean\$3 or wash\$3) and (wafer or semiconductor or substrate or workpiece) near10 (roller or wheel) and (nozzle or fluid near5 inject\$3) near10 (move or moving or movable or adjust\$3 or angl\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 15:20

S24	55	"134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (clean\$3 or wash\$3) and (wafer or semiconductor or substrate or workpiece) near10 (roller or wheel) and (nozzle or fluid near5 inject\$3) near10 (move or moving or movable or adjust\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2006/01/12 15:22
S25	12	(wafer or semiconductor or substrate or workpiece) near5 (plurality or multiple or several) and (wafer or semiconductor or substrate or workpiece) near10 rotat\$3 near5 (roller or wheel) near10 (motor or engine) and (nozzle or fluid near5 inject\$3) near5 (adjust\$3 or mov\$3 or movable)	US-PGPUB; USPAT	OR	ON	2006/01/13 09:52
S26	1990	(rotat\$4 near5 plurality near5 (wafer or semiconductor or substrate or workpiece))	US-PGPUB; USPAT	OR	ON	2006/01/13 11:04
S27	190	(rotat\$4 near5 plurality near5 (wafer or semiconductor or substrate or workpiece) near5 (wheel or roll\$3))	US-PGPUB; USPAT	OR	ON	2006/01/13 17:16
S28	67	(rotat\$4 near5 (plurality or multiple) near5 (wafer or semiconductor or substrate or workpiece) near5 (clean\$3 or wash\$3))	US-PGPUB; USPAT	OR	ON	2006/01/13 17:22
S29	10	"5862823"	US-PGPUB; USPAT	OR	ON	2006/01/13 17:22